	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e	r D e f i n	E r o r
1	BRS		sti with gate near (oxide or dielectric or insulating) with semiconductor	1	2004/06/24 21:06			0
2	BRS		sti with gate near (oxide or dielectric or insulating) with semiconductor and gate near electrode with semiconductor with pattern\$6 and drain and source and ion near implant\$6 and ((thermal or heat) with treat\$6) or anneal\$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 19:55			0
3	BRS	46	insulating) with semiconductor and resistan\$6 with region	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 19:59			0
4	BRS	5		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 20:00			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e n	r D e f i n	o r
5	BRS	16	with region and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 20:00			0
6	BRS	11	with electrode sti with gate near (oxide or dielectric or insulating) with semiconductor and gate near electrode with semiconductor with pattern\$6 and drain and source and ion near implant\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 20:01			Ο
7	BRS	19	with semiconductor and gate near electrode with semiconductor with pattern\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/02 20:01			0
8	BRS		-	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 17:25			0

	Тур	Hi ts	Search Text	DBs '	Time Stamp	m m e	r D e f	Errors
9	BRS	55	! - • - .	E .	2004/05/05 17:26			0
10	BRS	45	insulating) with	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/05 17:27			0
11	BRS	12	sti with resist\$7 and gate near (oxide or dielectric or insulating) with semiconductor and mask with resist\$7 and ion with implant\$7 and spacer with resist\$7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/07 14:42			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e	e f i	E r r
12	BRS	6	sti with (resista\$7 or resisto\$6) and gate near (oxide or dielectric or insulating) with semiconductor and mask with resist\$7 and ion with implant\$7 and spacer with (resisto\$7 or resista\$7)		2004/05/07 14:47			0
13	BRS	26	(isolat\$6 or field adj oxide) with (resista\$7 or resisto\$6) and gate near (oxide or dielectric or insulating) with semiconductor and mask with resist\$7 and ion with implant\$7 and spacer with (resisto\$7 or resista\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/07 14:49			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e	r D e f	E r r o r
14	BRS	24	(isolat\$6 or field adj oxide) with (resista\$7 or resisto\$6) and gate near (oxide or dielectric or insulating) with semiconductor and mask with (resisto\$7 or resista\$6) and ion with implant\$7 and spacer with (resisto\$7 or resista\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/07 16:16			0
15	BRS		(isolat\$6 or field adj oxide) with (resista\$7 or resisto\$6) and gate with mask with (resisto\$7 or resista\$6) and ion with implant\$7 and spacer with (resisto\$7 or resista\$7) and source and drain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/07 16:17			0
16	BRS		5013678.URPN.	USPAT	2004/05/07 16:50			0
17	BRS	15	5585302.URPN.	USPAT	2004/05/07 17:03			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m e	D e f i n	r
18	BRS	34 1	<pre>implant with resistance with (source or drain) and (field adj oxide or isolat\$6)</pre>	I	2004/06/24 21:07			0
19	BRS	23 71	<pre>implant\$6 with resist\$6 with (source or drain) and (field adj oxide or isolat\$6)</pre>		2004/06/24 21:09			0
20	BRS	11 30	with (source	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/24 21:11			0
21	BRS			USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/24 21:12			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e	ErrorDefinitio	E r o r
22	BRS	13 4	implant %6 with (resista %6 or resisto %6) with (source or drain) and (field adjoxide or isolat %6) and (mask or photoresist) with (resista %6 or resisto %6) and		2004/06/24 21:14			0
23	BRS	75		JPO; DERWENT;	2004/06/24 21:15			0

	Тур	Hi ts	Search Text	DBs	Time Stamp	m m e n t	ErrorDefinitio	Errors
24	BRS		(mask or photoresist) with (resista\$6 or resisto\$6) and ldd and (heat\$6 or thermal or anneal\$6) with activat\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/24 23:10			0
25	IS& R	2	("20020127791").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/06/24 23:10			0

IBM_LDB